

STRUCTURAL CHARACTERIZATION OF YTTRIA STABILIZED ZIRCONIA
THIN FILM DEPOSITED BY MAGNETRON SPUTTERING

NURHAMIZAH BINTI AHMAD RUSLI

A thesis submitted in fulfilment of the
requirements for the award of the degree of
Doctor of Philosophy

Faculty of Science
Universiti Teknologi Malaysia

JUNE 2020

DEDICATION

My deepest appreciation goes to my family especially my late mother Kintan Binti Othman who passed away before she saw the results of her good work. Mothers are the constant motivation and source of true love. Also my dedication goes to my supervisors, friends and who are currently doing their PhD thesis. This journey involved more than 1000 difficulties, both fascinating and determination from our self and surrounding. I believed that this journey will acts as a platform for researcher and PhD students, particularly in the field of basic and applied physic, to showcase recent research findings, to explore new knowledge on the latest advancement, and importantly to improve the development of professional and social networking amongst the students. My best wishes to all of the PhD students for their remarkable dedication and difficulty in making this PhD thesis. May Allah's blessing be upon you.

ACKNOWLEDGEMENT

Thanks to Allah SWT for His grace, leading, guidance and giving this opportunity to make my dream success in completing the PhD study in physics. First of all, I would like to give my respect to my supervisor, Dr Rosnita Binti Muhammad who always gives me full of motivation, support, knowledge, inspiration and kindness during this study. Special thanks to my co-supervisor Assoc. Prof. Dr Sib Krishna Ghoshal who has given me a substantial assistance and moral support in completing this study. I would like to express my grateful thanks to my previous supervisor and all members in Long Term Research Grant Scheme (LRGS) grant for Solid Oxide Fuel Cell, Prof. Dr. Samsudi Sakrani, Assoc. Prof. Dr Zuhairi Ibrahim, Assoc. Prof. Dr Karim Deraman, Prof. Dr. Yusof Wahab and Prof. Dr. Hadi Nur. I would like to offer my heartfelt thanks to all my families and siblings. It gives me great pleasure to thank Assoc. Prof. Dr Nafarizal Nayan and Miss Ashraf from Universiti Tun Hussein Malaysia (UTHM) who have shown very encouraging support for teach me the sputtering equipment. For all the lab buddies Nuryasmin, Noraqidah, Nurfathirah, Norazilah, Norhidayah, and Shahirah, I wish you Good luck. I hope everyone will take this opportunity to create achievement in your own respective fields. Last but not least, thanks to Ministry of High Education (MoHE) for financial support through MyBrain15

ABSTRACT

Yttria stabilized zirconia (YSZ) thin film is of great interest as an ion-conductor for the electrolyte-electrode sandwich in solid oxide fuel cell (SOFC) applications. YSZ electrolytes have several advantages, but its applicability has been mainly limited because of the inability to synthesize YSZ films at low temperatures due to its high melting point. One way to overcome such limitation is to establish the YSZ structure by optimizing the percentage of crystallinity and densification of the thin film. The current study was focused on the comparative evaluation of crystallization and densification of dense-thin YSZ film for electrolyte in SOFC. The oxygen flow rate (0-50 sccm), substrate bias voltage (0-120 V), substrate temperature (200-300°C), and deposition time (30-120 min) were evaluated in order to develop dense-thin YSZ film with high crystallinity at low substrate temperatures by radio frequency (RF) magnetron sputtering. The deposition parameter controlled the general morphology and the film thickness, whereas the annealing parameter (300-600°C) affected the crystal orientation in thin films. The current study also determined the effects of the selected deposition parameters on the properties and structures of YSZ thin films. The produced thin films were characterized by glancing angle X-ray diffraction (GAXRD), field emission scanning electron microscopy (FESEM), atomic force microscopy (AFM), Raman spectroscopy, Fourier-transform infrared spectroscopy (FTIR) and transmission electron microscopy (TEM). Based on the results, a dense-thin YSZ film was produced with an average thickness of approximately 200 nm without oxygen flow. The GAXRD pattern of YSZ thin film revealed the existence of a columnar structure (cubic phases) with preferred growth along (200) lattice orientation. YSZ thin films grown at 120 V exhibited good homogeneity and uniformity (100 nm thick and 10-12 nm crystallite size) accompanied by a large microstrain along (111) lattice orientation. The sample obtained at the highest substrate temperature (300°C) revealed the lowest microstrain (0.028%) and the highest crystallinity (43%) with a non-columnar structure. The main effect of the deposition time (60 min) had the strongest effect on the lattice microstrain and the thickness of the YSZ thin film. In conclusion, the combined effects of the substrate temperature (300°C) and annealing factor (400°C) were successful in the development of dense-thin YSZ film with high crystallinity (60%) for potential electrolyte use in SOFCs.

ABSTRAK

Saput tipis Yttria Stabilize Zirconia (YSZ) telah menarik perhatian sebagai konduktor-ion dalam kepingan berapit elektrolit-elektrod untuk kegunaan sel api pepejal oksida. Kelebihan yang ditawarkan elektrolit YSZ selalu terbatas kerana sukar untuk disintesis pada suhu rendah akibat dari suhu takat didih yang tinggi. Bagi mengatasi kekurangan ini, YSZ ini akan disintesis dan dicirikan bagi mendapatkan struktur yang optimum melalui peratus kehomogen dan saput tipis yang padat. Penyelidikan ini fokus kepada penilaian perbandingan kehomogen dan padat saput tipis nanostruktur YSZ sebagai elektrolit. Memanipulasikan parameter percikan magnetron frekuensi radio (RF) termasuk kadar aliran oksigen (0-50 sccm), biasan voltan substrat (0-120 V), suhu substrat (200-300°C) dan masa pengendapan (30-120 minit), membolehkan untuk menghasilkan saput tipis yang padat dan tinggi homogen pada suhu substrat yang rendah. Parameter pertumbuhan mengawal morfologi dan ketebalan saput tipis amnya manakala kesan penyepuhlindapan (300-600°C) mempengaruhi orientasi kristal saput tipis. Kajian terkini mengkaji kesan parameter pertumbuhan terhadap sifat morfologi dan struktur YSZ. Saput tipis yang dihasilkan dicirikan menggunakan peralatan pembelauan sinar X-ray (GAXRD), mikroskop imbasan kesan medan electron (FESEM), mikroskop daya atom (AFM), raman spektroskopi, spektroskopi inframerah transformasi Fourier (FTIR) dan mikroskop elektron penghantaran (TEM). Berdasarkan hasil kajian, sampel padat ketebalan 200 nm diperolehi tanpa aliran oksigen. Paten sudut pembelauan X-ray saput tipis YSZ menunjukkan kewujudan struktur turus (fasa kubik) dengan (200) orientasi kekisi. Saput tipis YSZ yang ditumbuhkan pada 120 V menunjukkan kehomogenan yang baik dan seragam (tebal 100 nm dan saiz kristal dalam lingkungan 10-12 nm) disamping mikroterikan besar sepanjang (111) orietasi kekisi. Sampel pada suhu tertinggi substrat (300°C) menunjukkan mikroterikan paling rendah (0.028%) dan homogen tertinggi (43%) dengan struktur tidak turus. Kesan utama masa pertumbuhan (60 minit) menjadi pengaruh terkuat kepada mikroterikan kekisi dan ketebalan YSZ. Sebagai penutup, kesan penggabungan suhu substrat (300°C) dan faktor penyepuhlindapan (400°C) telah berjaya membina saput tipis YSZ dengan homogen tinggi (60%) dan padat berpotensi sebagai elektrolit dalam SOFC.

TABLE OF CONTENTS

	TITLE	PAGE
	DECLARATION	iii
	DEDICATION	iv
	ACKNOWLEDGEMENT	v
	ABSTRACT	vi
	ABSTRAK	vii
	TABLE OF CONTENTS	viii
	LIST OF TABLES	xi
	LIST OF FIGURES	xiii
	LIST OF ABBREVIATIONS	xviii
	LIST OF SYMBOLS	xix
	LIST OF APPENDICES	xx
CHAPTER 1	INTRODUCTION	1
1.1	Background of Study	1
1.2	Problem Statement	3
1.3	Objectives	5
1.4	Scope of the Study	6
1.5	Significance of Research	6
1.6	Thesis Organisation	7
CHAPTER 2	LITERATURE REVIEW	9
2.1	Introduction	9
2.2	Solid Oxide Fuel Cell	9
2.2.1	Component of Solid Oxide Fuel Cell	10
2.2.2	Electrolyte	12
2.2.3	Potential of Low Temperature Solid Oxide Fuel Cell	13
2.3	Properties of Yttria Stabilized Zirconia	14
2.3.1	Introduction	14
2.3.2	Crystal Structure of YSZ	15
2.3.3	Atomic Plane Orientation	20
2.3.4	Microstructure	21
2.3.5	Topography	23
2.3.6	Raman Analysis	24
2.3.7	FTIR Spectra	28
2.4	Nucleation and Growth Mechanism of Thin Film	30
2.4.1	Introduction	30

2.4.2	Growth Mechanism	30
2.4.3	Homogeneous Nucleation	32
2.4.4	Heterogeneous Nucleation	33
2.4.5	Thin Film Growth	35
2.5	Impact of Various Growth Parameter of Radio Frequency Magnetron Sputtering on YSZ Thin Film	39
2.5.1	Influences of Oxygen Content	40
2.5.2	Effects of Substrate Bias Voltage on Growth	40
2.5.3	Influences of Substrate Temperature of Growth	41
2.5.4	Effects of Deposition Time on Growth	42
CHAPTER 3	METHODOLOGY	49
3.1	Introduction	49
3.2	Preparation of Substrate	51
3.3	The YSZ Target	52
3.4	YSZ Thin Film Growth Process	53
3.4.1	Radio Frequency Magnetron Sputtering Setup	53
3.4.2	Growth Parameters	55
3.5	Characterization of Samples	58
3.5.1	Glancing Angle X-Ray Diffraction (GAXRD)	58
3.5.2	Raman Spectroscopy	61
3.5.3	Fourier Transform Infrared (FTIR) Spectroscopy	62
3.5.4	Transmission Electron Microscopy (TEM)	63
3.5.5	Field Emission Scanning Electron Microscopy (FESEM)	64
3.5.6	Energy Dispersive X-ray (EDX)	66
3.5.7	Atomic Force Microscopy (AFM)	67
CHAPTER 4	RESULTS AND DISCUSSION	69
4.1	Introduction	69
4.2	Impact of Oxygen Flow Rate on Structure and Morphology of YSZ Thin Film	70
4.2.1	Crystal Structure Analysis	70
4.2.2	Microstructures	73
4.2.3	Composition of YSZ Thin Film	76
4.3	Dependence of YSZ Thin Film on Substrate Bias Voltage	78
4.3.1	X-Ray Diffraction Pattern	78
4.3.2	Morphological Properties	88
4.3.3	EDX Spectra	92
4.3.4	AFM Images and Particle Size Distribution	94

4.3.5	Raman Spectra	97
4.3.6	Fourier-transform Infrared (FTIR) Spectra	104
4.4	Substrate Temperature Dependence Structure and Morphology of YSZ Thin Film	108
4.4.1	Crystallinity	108
4.4.2	Microstructures Analysis	112
4.4.3	Elemental Composition	114
4.4.4	AFM Topography	116
4.4.5	Raman Spectrum	119
4.5	Annealing Temperature Dependent Structure and Morphology of YSZ Thin Film	122
4.5.1	GAXRD Patterns	122
4.5.2	AFM Micrographs	127
4.5.3	FESEM Micrographs	131
4.5.4	EDX Spectrum and Maps	134
4.5.5	TEM Micrographs	136
4.6	Deposition Time Dependent on YSZ Thin Film	138
4.6.1	Crystallinity	138
4.6.2	AFM Images	142
4.7	Comparative Analysis	145
CHAPTER 5	CONCLUSIONS AND FURTHER WORKS	153
5.1	Conclusions	153
5.2	Further Works	156
	REFERENCES	157
	LIST OF PUBLICATIONS	176

LIST OF TABLES

TABLE NO.	TITLE	PAGE
Table 2.1	Raman data of YSZ thin film deposited at different technique	27
Table 2.2	Findings from previous work relate to YSZ thin film deposited using sputtering	43
Table 3.1	Physical, mechanical and thermal properties of YSZ	52
Table 3.2	Experimental parameters of YSZ thin film	57
Table 4.1	Thickness of YSZ thin film	91
Table 4.2	Surface roughness and mean grain size of YSZ thin film in AFM analysis	95
Table 4.3	Raman band position of YSZ thin film	101
Table 4.4	Assignment of the FTIR transmittance bands	106
Table 4.5	Structural properties of YSZ thin film from X-ray diffraction analysis	111
Table 4.6	Ratio of cubic: tetragonal of YSZ thin film at different substrate temperature	120
Table 4.7	Raman mode of YSZ thin film deposited at different substrate temperature	120
Table 4.8	The structural properties of YSZ thin film from X-ray diffraction data	123
Table 4.9	Mean particles size and RMS surface roughness of the YSZ thin films obtained from AFM micrograph analyses.	127
Table 4.10	Crystallite size, microstrain and relative crystallinity of YSZ thin film deposited at different time	141
Table 4.11	Crystallinity and structure of YSZ thin film at different oxygen content	146
Table 4.12	Crystallinity and structure of YSZ thin film at different substrate bias voltage	147
Table 4.13	Crystallinity and structure properties of YSZ thin film at different substrate temperature	148
Table 4.14	Annealing temperatures of YSZ thin film after sputtering deposition	150

Table 4.15 Crystallinity and structural properties of YSZ thin film at different deposition time

151

LIST OF FIGURES

FIGURE NO.	TITLE	PAGE
Figure 2.1	A sketch of an SOFC illustrating the working principle [39]	11
Figure 2.2	Crystal structure of YSZ with lattice constant $a = 0.512$ nm [58]	16
Figure 2.3	Stress and texture development during sputtering of yttria, zirconia, and yttria stabilized zirconia films on Si substrates [63]	18
Figure 2.4	(a) XRD of YSZ samples deposited at different substrate temperatures and bias voltages, (b) XRD of YSZ samples deposited without substrate temperature at various bias voltage [64].	19
Figure 2.5	Selected- area electron diffraction (SAED) of a (a) (111) and (b) (100) oriented YSZ thin film [54]	20
Figure 2.6	FESEM images of bilayer YSZ thin film at thickness 500 nm deposited using pulse laser (PLD) and spray pyrolysis (SP) deposition [20].	22
Figure 2.7	Raman spectra for YSZ thin film deposited [14]	25
Figure 2.8	FT-IR spectra of a burned YSZ nano-clusters [71]	28
Figure 2.9	The stages of nucleation and film formation on substrate [81]	31
Figure 2.10	The mechanism growth of thin film and 1D structure [82].	32
Figure 2.11	(a) Heterostructure of Pt/GDC/BZY/Si ₃ N ₄ ; (b) TEM image of the Pt/GDC/BZY; (c) Dislocations is observed in the GDC interlayer (“⊥” labels); (d) The corresponding inverse FFT calculated the image of the dotted region in (c) [45].	35
Figure 2.12	Two types of Volmer –Weber growth mode [86]	36
Figure 2.13	Modes of growth of film: (a) Frank–vander Merwe layer growth (b) Stranski-Krastanov layer plus island growth and (c) Volmer–Weber island growth [81].	38
Figure 2.14	Representation of sputtering technique. The impact of an atom or ion on a surface produces sputtering from the surface [88]	39

Figure 3.1	Flowchart of the YSZ thin film growth and characterization	50
Figure 3.2	Glass substrates (SiO_2) were cut and be used as a base for YSZ thin film deposition	51
Figure 3.3	Target disk of YSZ	52
Figure 3.4	(a-c) RF and DC magnetron system at UTHM used for thin film deposition	54
Figure 3.5	Schematic of glancing angle x-ray diffraction (GAXRD) for surface, interface and thin film analysis	59
Figure 3.6	Picture of the scratched sample.	64
Figure 3.7	Schematic architecture of field emission scanning electron microscope	65
Figure 3.8.	Amount of atom detected were present in terms of atomic weight %	66
Figure 3.9	Schematic of AFM working principle	67
Figure 4.1	GAXRD patterns of all grown YSZ films (a) with glancing angle, (b) without glancing angle, (c) 0 sccm, (d) 25 sccm, (e) 50 sccm, (f) 0 sccm 600 °C, (g) 25 sccm 600 °C, (h) 50 sccm 600 °C, (i) 25 sccm 750 °C and (j) 50 sccm 750 °C.	71
Figure 4.2	Refinement of GAXRD at (111) orientation	72
Figure 4.3	FE-SEM images of surface morphology and cross section of YSZ thin film for oxygen flow rate of (a) (b) 0 sccm, (c) (d) 25 sccm (e) (f) 50 sccm (g) (h) 0 sccm annealed at 600 °C, and (i) 0 sccm annealed at 750 °C	74
Figure 4.4	O_2 content dependent elemental traces in the YSZ thin film	76
Figure 4.5	Compositional analysis of YSZ thin film with O_2 flow rate at (a) 0 sccm (b) 25 sccm (c) 50 sccm. Left side refers to cross section view of FESEM images while right side shows EDX spectra.	77
Figure 4.6	X-ray diffraction of YSZ thin films thin film deposited at different substrate bias voltage for 1 hour	79
Figure 4.7	Refinement of GAXRD pattern fitted to Gaussian (solid curve) for the four major peaks (a) [111], (b) [200], (c) [220] and (d) [311].	80
Figure 4.8	Williamson-Hall plots	82

Figure 4.9	Relationship between crystallite size and lattice microstrain of YSZ thin film deposited at different substrate bias voltage	82
Figure 4.10	Refinement of GAXRD pattern fitted to Gaussian (solid curve) for the four major peaks (a) (111), (b) (200), (c) (220) and (d) (311).	84
Figure 4.11	Lattice microstrain along four significant crystal lattice orientations.	86
Figure 4.12	FESEM images of all YSZ thin films with (a,c,e and g) top-view, and (b,d,f,and h) cross-sectional view.	89
Figure 4.13	Cross-sectional FESEM images showing scanned area (rectangular box) and the corresponding EDX spectra of YSZ thin films (a) 0V, (b) 40V, (c) 120V, and (d) 120V-600 °C.	92
Figure 4.14	Detected elements (wt%) in the YSZ thin films obtained using EDX spectral analysis.	93
Figure 4.15	AFM images and histogram of the grain size distribution on YSZ thin film	96
Figure 4.16	Raman spectra of YSZ thin film	97
Figure 4.17	FTIR spectra of the studied YSZ thin films	104
Figure 4.18	GAXRD diffraction of YSZ thin film at different substrate temperature	109
Figure 4.19	Refinement of GAXRD fitted to Gaussian (solid curve) for the four major peaks (a) (111), (b) (200), (c) (220) and (d) (311).	110
Figure 4.20	Lattice microstrain of YSZ thin film at various substrate temperatures	111
Figure 4.21	Relationship of crystallite size and lattice microstrain at various substrate temperature	111
Figure 4.22	FE-SEM images of YSZ thin film microstructure at different substrate temperature (a, c, e, g) surface morphology. (b, d, f, h-) cross-section images.	113
Figure 4.23	(a-c) Surface morphology of YSZ thin film with EDX spectrum and elemental distribution	114
Figure 4.24	Substrate temperature dependent elemental traces in the surface morphology of YSZ thin film	115
Figure 4.25	EDX point analysis of YSZ thin film at 200, 250 and 300 °C substrate temperature at cross section area	115

Figure 4.26	AFM images and surface roughness of YSZ thin film surface morphology with different substrate temperatures (a-A) 200 °C, (b-B) 250 °C and (c-C) 300 °C	116
Figure 4.27	AFM images of YSZ thin film and particle size distribution (histogram) with different substrate temperature (a) 200, (b) 250 and (c) 300 °C	118
Figure 4.28	Raman spectra of YSZ thin film at different substrate temperatures	119
Figure 4.29	Refinement of Raman spectra for YSZ thin film at different substrate temperatures (a) 250 °C (b) 250 °C and (c) 300 °C	121
Figure 4.30	X-ray diffraction pattern of YSZ thin film at different annealing temperature (a) YSZ target (b) as deposited (c) 380 °C (d) 400 °C (e) 450 °C (f) 500 °C and (g) 600 °C	122
Figure 4.31	Williamson-Hall plots	125
Figure 4.32	Lattice spacing of YSZ thin film without (RT) and with annealing temperature at 380-600 °C	126
Figure 4.33	The relative crystallinity of YSZ thin film without and with annealing temperature at 380-600 °C	126
Figure 4.34	3D AFM images of YSZ thin films (a) as-deposited and annealed at (b) 380 °C, (c) 400 °C, (d) 450 °C, (e) 500 °C, and (f) 600 °C	128
Figure 4.35	FESEM images of YSZ thin film (a, c, e and g) Top view, (b, d, f, h) Cross section	132
Figure 4.36	FESEM and elemental distribution images of the surface morphology of the as deposited YSZ thin film	134
Figure 4.37	(a,c) Surface morphology of as deposited YSZ thin film with (b,d) EDX spectrum and weight percent of YSZ element with Zr, Y and O element	135
Figure 4.38	TEM image of YSZ thin film (a) (b) 400 °C and (c) (d) 500 °C , inset shows selected area electron diffraction (SAED)	137
Figure 4.39	GAXRD spectra of YSZ thin film deposited at (a) 30 (b) 60 (c) 75 (d) 90 and (e) 120 minutes	138
Figure 4.40	Relative crystallinity at different lattice orientation (insert: Refinement for four intense peaks)	139
Figure 4.41	Texture coefficient at different lattice orientation for YSZ thin film deposited at 60, 75, 90 and 120 minute.	140

Figure 4.42	Williamson-Hall plots for YSZ thin film	141
Figure 4.43	AFM images of YSZ thin film at deposition time (a) 60, (b) 75, (c) 90 and (d) 120 minute	144

LIST OF ABBREVIATIONS

YSZ	-	Yttria Stabilized Zirconia
UTHM	-	Universiti Tun Hussein Malaysia
DC	-	Direct Current
RF	-	Radio Frequency
Y ₂ O ₃	-	Yttria
GAXRD	-	Glancing Angle X-ray Diffraction
SAED	-	Selected Area Electron Diffraction
SOFC	-	Solid Oxide Fuel Cell
PLD	-	Pulse Laser Deposition
A _{1g}	-	Singly Degenerate (Symmetric)
B _{1g}	-	Singly Degenerate (Anti-Symmetric)
E _g	-	Doubly Degenerate
F _{2g}	-	Triply Degenerate (Symmetric)
NA	-	Not Applicable
FHWM	-	Full width at half maximum intensity
m-YSZ	-	Monoclinic Yttria Stabilized Zirconia
t-YSZ	-	Tetragonal Yttria Stabilized Zirconia
c-YSZ	-	Cubic Yttria Stabilized Zirconia
IR	-	Infra-Red
UV	-	Ultra-Violet
EEDF	-	Electron Energy Distribution Function
TEM	-	Transmission Electron Microscopy
FESEM	-	Field Emission Scanning Electron Microscopy
AFM	-	Atomic Force Microscopy
FTIR	-	Fourier Transform Infrared
EDX	-	Energy Dispersive X-Ray
JCPDS	-	Joint Committee on Powder Diffraction Standards
ICSD	-	International Centre for Diffraction Data
OCV	-	Open Circuit Voltage
FCC	-	Face Centre Cubic

LIST OF SYMBOLS

ε	-	Microstrain
γ	-	Surface energy per unit area
D	-	Crystallite size
d	-	Lattice spacing
V	-	Volt
MHZ	-	Mega hertz
sccm	-	Standard cubic centimetres per minute
W	-	Watt
Å	-	Angstrom
A	-	Area
ν	-	Rayleigh scattering
K	-	Shape factor
GPa	-	Giga pascal
wt%	-	Weight percent
mTorr	-	Millitorr
deg.	-	Degree
a.u.	-	Arbitrary unit
keV	-	Kiloelectron volts
ohm	-	Electrical resistance
mW	-	Milliwatt
MgO	-	Magnesium oxide
O ²⁻	-	Ion oxygen

LIST OF APPENDICES

APPENDIX	TITLE	PAGE
Appendix A	YSZ X-Ray diffraction patterns for the YSZ target materials using with and without glancing angle at 1.5° (GAXRD). And JCPDS No. 1468	173
Appendix B	Area under curve at different orientation calculated by using Origin software (a) 60, (b) 75, (c) 90 and (d) 120 minute	174
Appendix C	Sandwich structure of Platinum/YSZ/ Platinum thin film deposited onto sapphire substrate	175

CHAPTER 1

INTRODUCTION

1.1 Background of Study

The reversible reaction of the fuel cell was first reported scientifically by Sir William Grove in 1839 [1]. Fifty years later, in 1889, a fuel cell using coal gas as fuel was designed by Charles Langer and Ludwig Mond. The concept of Nernst Diffusion Layer was established by Nernst in 1899, which was later interpreted as Nernst's law for gas-ion transport in electrolytes [2]. The electrolyte, generally known as fast-ion conductors, consists of a highly dense structural material intended to prevent the direct mixing of fuel gas (hydrogen) and oxidising gas (oxygen) [3].

Nowadays, a variety of industrial resources such as coal, oil and natural gas have been wasted with the energy loss ratio of approximately 65% for traditional central power plants and 10% for fuel cells. Despite these advantages, successful attempts were made to assess the potential of electrochemical devices such as solid oxide fuel cells (SOFCs) [3,4]. Recently, considerable progress has been made in the commercial use of low-temperature SOFC thin-film, covering many existing and emerging applications. Much of the previous research on low-temperature SOFCs (LT-SOFCs) have described the role of the solid-oxide crystal structure in facilitating ion movements from one site to another at operating temperatures down to 300-500 °C [5-7].

In general, thin-films with micro- and nano-film electrolyte nanostructures have become increasingly important in the research industry; they have become attractive alternatives to conventional methods, such as powder sieving, compaction, sol-gel, chemical deposition, hydrothermal, photoelectrochemical, liquid phase and extrusion. These corresponding methods are usually impossible to synthesise at low temperatures when compared to direct current (DC) or radiofrequency (RF)

magnetron sputtering. The thin-films offer a number of significant advantages and attractions over bulk materials: (i) Thin-film structures are almost always compact, especially when the structure is produced in a non-columnar microstructure that occupies pinhole-free films [8]. (ii) Thin-film is subjected to stress/strain effect, grain growth, microstructure evolution and phase transformation, which influence the bonding between the film and substrate. This factor also leads to the formation of phases, surface microstructures and film thicknesses that are important for electrolyte applications [9]. (iii) The thin-film of a small thickness (100 nm) may have the void of blocking the grain boundary perpendicular to the current flow, thus reducing the contribution of electron conductivity [10]. (iv) Thin-film systems may be adopted by manipulating factors such as ionic defects, concentration, mobility, structural orientation, microstructure, grain boundary and heterostructure interfaces. Therefore, the creation of well-designed nanostructures with two or three dimensions is difficult to achieve in bulk materials [11,12]. (v) Thin-film nanotechnology is safe with a relatively low environmental impact because of its ability to deposit high melting point oxides at low annealing/substrate temperatures and is compact in size [13].

The performance of Ytria Stabilised Zirconia (YSZ) based thin-film electrolyte materials are described in terms of crystallinity (purity) and density (compact or non-columnar). The crystallinity indicates the oxygen vacancy structure or the crystal rate of the desired structure, whereas the density indicates the degree of structure enrichment [14–16]. Furthermore, these pieces of literature have established different theories that describe the initial stages of the YSZ growth mechanism such as the challenge of depositing dense YSZ thin-film and the high melting temperature (2730 °C) for cubic YSZ growth.

To date, the effects of magnetron sputtering deposition have not yet been empirically studied on the growth of YSZ nano-thin film; therefore, the correlation between grain growth and stress strain evolution as an electrolyte has not been reported. The order of the oriented crystal structure clearly affects the mixing of microstructure and conductivity. Besides that, thermodynamics is one of the aspects of consideration. This research aims to determine whether nanocrystalline YSZ structure and nanofilm thickness can be produced using the RF magnetron deposition

technique. The Gibbs free energy of formation (G_f), per cent crystallinity, phase identification, morphology and thickness of YSZ were analysed in this study. The findings of this research will help to develop high-performance electrolytes by understanding the relationship among the following factors: structural evolution pattern, percentage of crystallinity, morphology and physicochemical properties.

1.2 Problem Statement

YSZ is a ceramic material that does not have excellent conductivity at low temperatures. Nevertheless, they need a high-temperature operation (900-1000 °C) to maintain their ionic conduction and electrochemical performance. During this operation, electrodes, electrolytes, and interconnectors covering the structure of SOFCs are subjected to physical and chemical modifications that lead to deterioration. Therefore, in order to overcome this issue, SOFCs with high-resistance materials can be easily developed to be operated at low temperatures especially in the presence of thin-film technology. Indeed, YSZ thin-film, which simultaneously has a high value of crystallinity and ionic conductivity, would lead to a thin and dense-thin layer [17–19]. However, this is contrary to the findings of equiaxed and columnar nanostructures from previous [20,21] studies.

Most previous studies [22–25] have considered the YSZ film to have: (1) dense equiaxed grains; (2) dense structure without voids/holes with cubic phases; (3) non-columnar structures without dual phase of YSZ thin-film showed better performance of gas tightness and electrochemical reactions compared to cubic phases with columnar structure. On the other hand, few studies [26,27] indicated that the YSZ film, consisting of columnar grains, can still reveal high conductivity and consistency of cell performance.

Furthermore, the crystal orientation and texture coefficient observed on the YSZ thin-film structure may add significant differences to the overall electrolyte properties and cause a moderate loss in crystallinity. Sometimes, the developed strong (220) preferential orientation is considered to have strong texture (stable

microstructure) compared to (111) and (200) orientations [9]. On the other hand, it has been shown that the higher intensity along (111) lattice orientation could lead to the formation of dense, less-defective, and restrained columnar grain as studied by S nderby et al.[28].

Generally, in YSZ thin-film, the crystallinity of the nano-thin film layer is slightly higher than that of the micro thin-film. However, the development of ultra-thin film electrolytes would result in non-oriented or defective crystal structure due to the irregular packing of atoms and the incomplete coalescence of grain growth, leading to a significant degree of crystallinity. Therefore, the quality of YSZ thin-film depends on the thickness of the entire thin-film and is also directly proportional to microstructure, morphology and texture coefficient [29]. In addition to several analyses, such as per cent crystallinity at (111) orientation, the crystallinity area of the YSZ structure was carried out in an attempt to study and correlate the growth parameter with the YSZ growth evolution. The results from glancing angle X-ray diffraction (GAXRD) showed four intense peaks for different growth parameters, which were desirable from a practical standpoint in the majority of cases. To date, few investigations had been conducted elucidating the relationship between the parameters mentioned above (i.e. oxygen flow rate, substrate bias voltage and substrate temperature) and the structural and morphological properties of YSZ; unfortunately, most of their studies have neglected interaction effects between these (111), (200), (220) and (311) peak correlations.

Hence, this study contributes to our knowledge by addressing three important issues that play a key role in determining the crystallinity of YSZ thin-film. First, the fragile thin-film must properly adhere to the substrate as reported by Jiang and Hertz [26]. Second, the crystal orientation, which had an adverse effect on YSZ grain growth, studied by Hill et al. [24] and Sochugov et al. [30]. Third, the growth rate with optimum thickness resulting from different interdiffusion/adhesion, grain growth and texture evolution [31]. Despite the importance of YSZ as ionic transport in a low-temperature solid oxide system, there is still a lack of systematic understanding of how YSZ thin-film grows at low temperatures through the use of

RF magnetron sputtering that contributes to phase transformation, microstructure transformation and structural formation of YSZ.

Moreover, many researchers used the liquid vapour method for the preparation of deposition, such as pulse laser deposition (PLD) and atomic layer deposition (ALD), to produce YSZ nano-thin film as an electrolyte. There is an interesting finding of the successful deposition of RF magnetron sputtering due to its ability to deposit high melting point oxides at relatively low substrate temperatures. So far, the deposition rate using RF magnetron sputtering is very low, and therefore difficult to produce a completed dense-thin film. In this study, RF magnetron sputtering is hypothesised to produce an innovative modification because the vacuum-assisted deposition process technique for depositing a thin-film material atom-by-atom or molecule-by-molecule onto a solid structure can be conducted in a chamber. As a result, the outcome of this research should lead to an understanding of the growth of YSZ phases and the morphological structure of thin-film for electrolyte characterisation.

1.3 Objectives

1. To prepare YSZ thin-film using various growth parameters such as oxygen flow rate, substrate temperature, substrate bias voltage, deposition time and annealing temperature.
2. To analyse the structural and morphological parameters of the prepared YSZ thin-film as a function of the growth parameter.
3. To determine the effects of the growth parameter on improving the crystallinity and density of YSZ thin-film for optimisation.

1.4 **Scope of the Study**

Based on the background of this study, the scope of this study includes:

1. RF magnetron sputtering under various growth parameters, such as oxygen flow rate, substrate bias voltage, substrate temperature and deposition time, was used for YSZ thin-film growth. The post-treatment process (annealing temperature) was carried out between 380 and 600 °C.
2. Fine structural details such as percentage of crystallinity, texture coefficient, micro strain, crystallite size, molecule vibration and chemical bonding of YSZ thin-film were determined using GAXRD, Raman spectroscopy and FTIR. This was followed by the determination of the morphological properties of YSZ thin-film such as thickness, grain size, surface roughness, element distribution and lattice structure using FESEM, AFM and TEM.
3. Optimising the resulting YSZ thin-film by comparing different properties using the percentage of crystallinity and dense structure.

1.5 **Significance of Research**

The role of phases and structure of YSZ as an electrolyte has been extensively studied. Furthermore, YSZ materials are particularly useful in an environment requiring a high level of solid oxide (O^{2-}) conductor that is strongly affected by the temperature. This could be explained by the ionic conduction that is easier at higher temperatures as ions vibrate more vigorously and the defect concentrations are higher. Nevertheless, the ability of SOFC to operate at low temperatures has increased the interest among researchers to extend its application to operating temperatures down to 300-500 °C. Thin-film nanostructures have been developed in an attempt to optimise the ion conductivity compared to the bulk and membrane structure. Moreover, the results from this research will contribute to the enhanced deposition of YSZ thin-film by identifying the suitable growth parameter

and fabrication parameters for improved electrolyte-electrode performance and will also contribute to the development of SOFC that can operate at low temperatures.

1.6 **Thesis Organisation**

The research outline of this study consists of five chapters. Chapter 1 presents the introduction of the study, the problem statement, the specific objectives, scopes, the significance of the study and the research outline. Chapter 2 summarises the available literature on SOFC, electrolyte, YSZ properties and thin-film growth deposition. Chapter 3 summarises the experiments and the characterisation of the thin-film produced in this study. Chapter 4 presents the results and discussions of the experiments performed. Chapter 5 summarises the conclusions of the work presented in this thesis and the suggestions for future work.

REFERENCES

- [1] W.R. Grove, XXIV. On voltaic series and the combination of gases by platinum, *Philos. Mag. Ser. 3.* 14 (1839) 127–130. doi:10.1080/14786443908649684.
- [2] T. Liu, X. Zhang, X. Wang, J. Yu, L. Li, A review of zirconia-based solid electrolytes, *Ionics (Kiel)*. 22 (2016) 2249–2262. doi:10.1007/s11581-016-1880-1.
- [3] M. Kuhn, T.W. Napporn, Single-Chamber solid oxide fuel cell technology- from its origins to today's state of the art, *Energies*. 3 (2010) 57–134. doi:10.3390/en3010057.
- [4] S. Halimah, S. Munira, M. Hafiz, D. Othman, M.A. Rahman, Co-extruded dual-layer hollow fiber with different electrolyte structure for a high temperature micro-tubular solid oxide fuel cell, *Int. J. Hydrogen Energy*. 42 (2016) 9116–9124. doi:10.1016/j.ijhydene.2016.06.044.
- [5] T. Mukai, T. Fujita, S. Tsukui, K. Yoshida, M. Adachi, K.C. Goretta, Effect of rate on pulsed laser deposition of yttria-stabilized zirconia electrolyte thin films for SOFCs, *J. Fuel Cell Sci. Technol.* 12 (2015) 031002. doi:10.1115/1.4029423.
- [6] T. Kariya, H. Tanaka, T. Hirono, T. Kuse, K. Yanagimoto, K. Uchiyama, M. Henmi, M. Hirose, I. Kimura, K. Suu, H. Funakubo, Development of a novel cell structure for low-temperature SOFC using porous stainless steel support combined with hydrogen permeable Pd layer and thin film proton conductor, *J. Alloys Compd.* 654 (2016) 171–175. doi:10.1016/j.jallcom.2015.09.109.
- [7] I. Chang, J. Bae, J. Park, S. Lee, M. Ban, T. Park, Y.H. Lee, H.H. Song, Y.B. Kim, S.W. Cha, A thermally self-sustaining solid oxide fuel cell system at ultra-low operating temperature (319 °C), *Energy*. 104 (2016) 107–113. doi:10.1016/j.energy.2016.03.099.
- [8] S. Hong, D. Lee, Y. Lim, J. Bae, Y.B. Kim, Yttria-stabilized zirconia thin films with restrained columnar grains for oxygen ion conducting electrolytes, *Ceram. Int.* 42 (2016) 16703–16709. doi:10.1016/j.ceramint.2016.07.123.

- [9] R. Frison, S. Heiroth, J.L.M. Rupp, K. Conder, E.J. Barthazy, E. Müller, M. Horisberger, M. Döbeli, L.J. Gauckler, Crystallization of 8 mol % yttria-stabilized zirconia thin-films deposited by RF-sputtering, *Solid State Ionics*. 232 (2013) 29–36. doi:10.1016/j.ssi.2012.11.014.
- [10] S. Ji, G.Y. Cho, W. Yu, P. Su, M.H. Lee, S.W. Cha, Plasma-enhanced atomic layer deposition of nanoscale yttria-stabilized zirconia electrolyte for solid oxide fuel cells with porous substrate, *Appl. Mater. Interfaces*. 7 (2015) 2998–3002. doi:10.1021/am508710s.
- [11] E. Fabbri, D. Pergolesi, E. Traversa, Ionic conductivity in oxide heterostructures: The role of interfaces, *Sci. Technol. Adv. Mater.* 11 (2010). doi:10.1088/1468-6996/11/5/054503.
- [12] A. Kushima, B. Yildiz, Oxygen ion diffusivity in strained yttria stabilized zirconia: where is the fastest strain?, *J. Mater. Chem.* 20 (2010) 4809. doi:10.1039/c000259c.
- [13] M. Asadikiya, H. Sabarou, M. Chen, Y. Zhong, Phase diagram for a nano-yttria-stabilized zirconia, *RSC Adv.* 6 (2016) 17438–17445. doi:10.1039/C5RA24330K.
- [14] S. Heiroth, R. Frison, J.L.M. Rupp, T. Lippert, E.J. Barthazy, E. Müller, M. Döbeli, K. Conder, A. Wokaun, L.J. Gauckler, Crystallization and grain growth characteristics of yttria-stabilized zirconia thin films grown by pulsed laser deposition, *Solid State Ionics*. 191 (2011) 12–23. doi:10.1016/j.ssi.2011.04.002.
- [15] D. Dubbink, G. Koster, G. Rijnders, Growth mechanism of epitaxial YSZ on Si by Pulsed Laser Deposition, *Sci. Rep.* 8 (2018) 2–11. doi:10.1038/s41598-018-24025-7.
- [16] T.H. Yeh, R. De Lin, J.S. Cherng, Significantly enhanced ionic conductivity of yttria-stabilized zirconia polycrystalline nano-film by thermal annealing, *Thin Solid Films*. 544 (2013) 148–151. doi:10.1016/j.tsf.2013.03.134.
- [17] J.S. Park, M. Engineering, E. Energy, T. Division, Improved oxygen surface exchange kinetics at grain boundaries in nanocrystalline yttria-stabilized zirconia, 2 (2012) 107–111. doi:10.1557/mrc.2012.18.
- [18] A.A. Solovyev, N.S. Sochugov, S. V Rabotkin, A. V Shipilova, I. V Ionov, A.N. Kovalchuk, A.O. Borduleva, Application of PVD methods to solid oxide fuel cells, *Appl. Surf. Sci.* 310 (2014) 272–277.

- [19] S. Ji, J. An, D.Y. Jang, Y. Jee, J.H. Shim, S.W. Cha, On the reduced electrical conductivity of radio-frequency sputtered doped ceria thin film by elevating the substrate temperature, *Curr. Appl. Phys.* 16 (2016) 324–328. doi:10.1016/j.cap.2015.12.011.
- [20] R. Tölke, A. Bieberle-hütter, A. Evans, J.L.M. Rupp, L.J. Gauckler, Processing of Foturan glass ceramic substrates for micro-solid oxide fuel cells, *J. Eur. Ceram. Soc.* 32 (2012) 3229–3238. doi:10.1016/j.jeurceramsoc.2012.04.006.
- [21] A.A. Solov'ev, A. V. Shipilova, A.N. Koval'chuk, I. V. Ionov, S. V. Rabotkin, Comparison of characteristics of solid oxide fuel cells with YSZ and CGO film solid electrolytes formed using magnetron sputtering technique, *Russ. J. Electrochem.* 52 (2016) 662–668. doi:10.1134/S102319351607017X.
- [22] G. Jose La O, J. Hertz, H. Tuller, Y. Shao-Horn, Microstructural features of RF-sputtered SOFC anode and electrolyte materials, *J. Electroceramics.* 13 (2004) 691–695. doi:10.1007/s10832-004-5177-9.
- [23] R. Nédélec, S. Uhlenbruck, D. Sebold, V.A.C. Haanappel, H.P. Buchkremer, D. Stöver, Dense yttria-stabilised zirconia electrolyte layers for SOFC by reactive magnetron sputtering, *J. Power Sources.* 205 (2012) 157–163. doi:10.1016/j.jpowsour.2012.01.054.
- [24] N.S. Sochugov, A.A. Soloviev, A. V Shipilova, S. V Rabotkin, V.P. Rotshtein, I.T. Sigfusson, The effect of pulsed electron beam pretreatment of magnetron sputtered $ZrO_2:Y_2O_3$ films on the performance of IT-SOFC, *Solid State Ionics.* 231 (2013) 11–17. doi:10.1016/j.ssi.2012.11.001.
- [25] J. Sakali, B. Abakevi, S. Tamulevi, Influence of magnetron sputtering deposition conditions and thermal treatment on properties of platinum thin films for positive electrode–electrolyte – negative electrode structure, *Thin Solid Films.* 594 (2015) 101–108.
- [26] J. Jiang, J.L. Hertz, On the variability of reported ionic conductivity in nanoscale YSZ thin films, *J. Electroceramics.* 32 (2014) 37–46. doi:10.1007/s10832-013-9857-1.
- [27] D. Young, H. Keun, J. Woo, K. Bae, M.V.F. Schlupp, S. Won, M. Prestat, J. Hyung, Low-temperature performance of yttria-stabilized zirconia prepared

- by atomic layer deposition, *J. Power Sources*. 274 (2015) 611–618. doi:10.1016/j.jpowsour.2014.10.022.
- [28] S. Sønderby, A.J. Nielsen, B.H. Christensen, K.P. Almqvist, J. Lu, J. Jensen, L.P. Nielsen, P. Eklund, Reactive magnetron sputtering of uniform yttria-stabilized zirconia coatings in an industrial setup Zr / Y targets, *Surf. Coat. Technol.* 206 (2012) 4126–4131. doi:10.1016/j.surfcoat.2012.04.007.
- [29] M. Takayanagi, T. Tsuchiya, K. Kawamura, M. Minohara, K. Horiba, H. Kumigashira, T. Higuchi, Thickness-dependent surface proton conduction in (111) oriented yttria-stabilized zirconia thin film, *Solid State Ionics*. 311 (2017) 46–51. doi:10.1016/j.ssi.2017.09.003.
- [30] T. Hill, H. Huang, T. Hill, H. Huang, Fabricating pinhole-free YSZ sub-microthin films by magnetron sputtering for micro-SOFCs, *Int. J. Electrochem.* 2011 (2011) 1–8. doi:10.4061/2011/479203.
- [31] A. Banerjee, K.V.L. V Narayanachari, S. Raghavan, Effect of in situ stress on grain growth and texture evolution in sputtered YSZ / Si films, *RSC Adv.* 7 (2017) 17832–17840. doi:10.1039/c6ra28437j.
- [32] W. Wu, S.-A. Chen, Y.-C. Chiu, Design and control of an SOFC/GT hybrid power generation system with low carbon emissions, *Ind. Eng. Chem. Res.* 55 (2016) 1281–1291. doi:10.1021/acs.iecr.5b01961.
- [33] N. Duan, D. Yan, B. Chi, J. Pu, L. Jian, High performance anode-supported tubular solid oxide fuel cells fabricated by a novel slurry-casting method, *Sci. Rep.* 5 (2015) 5–8. doi:10.1038/srep08174.
- [34] L.S. Mahmud, a. Muchtar, M.R. Somalu, Challenges in fabricating planar solid oxide fuel cells: A review, *Renew. Sustain. Energy Rev.* 72 (2017) 105–116. doi:10.1016/j.rser.2017.01.019.
- [35] P. Coddet, H. Lin Liao, C. Coddet, A review on high power SOFC electrolyte layer manufacturing using thermal spray and physical vapour deposition technologies, *Adv. Manuf.* 2 (2013) 212–221. doi:10.1007/s40436-013-0049-7.
- [36] M. Irshad, K. Siraj, R. Raza, A. Ali, P. Tiwari, B. Zhu, A. Rafique, A. Ali, M. Kaleem Ullah, A. Usman, A brief description of high temperature solid oxide fuel cell's operation, materials, design, fabrication technologies and performance, *Appl. Sci.* 6 (2016) 75. doi:10.3390/app6030075.

- [37] R. Henne, Solid oxide fuel cells: A challenge for plasma deposition processes, *J. Therm. Spray Technol.* 16 (2007) 381–403. doi:10.1007/s11666-007-9053-4.
- [38] R. Ebrahim, M. Yeleuov, A. Issova, S. Tokmoldin, A. Ignatiev, Thin solid oxide fuel cell stack for low power applications, *Int. J. Eng. Sci. Innov. Technol.* 4 (2015) 146–151.
- [39] D. Beckel, A. Bieberle-Hütter, A. Harvey, A. Infortuna, U.P. Muecke, M. Prestat, J.L.M. Rupp, L.J. Gauckler, Thin films for micro solid oxide fuel cells, *J. Power Sources.* 173 (2007) 325–345. doi:10.1016/j.jpowsour.2007.04.070.
- [40] Z. Gao, L. V. Mogni, E.C. Miller, J.G. Railsback, S. a. Barnett, A perspective on low-temperature solid oxide fuel cells, *Energy Environmental Sci.* 9 (2016) 1602–1644. doi:10.1039/C5EE03858H.
- [41] Y.U. Liu, Z. Shao, *Electrolyte Materials for Solid Oxide Fuel Cells (SOFCs)*, (2013) 26–55.
- [42] J.H. Kennedy, Thin film solid electrolyte systems, *Thin Solid Films.* 43 (1977) 41–92.
- [43] W. Jung, J.L. Hertz, H.L. Tuller, Enhanced ionic conductivity and phase meta-stability of nano-sized thin film yttria-doped zirconia (YDZ), *Acta Mater.* 57 (2009) 1399–1404. doi:10.1016/j.actamat.2008.11.028.
- [44] A.A. Solovyev, A.M. Lebedynskiy, A. V Shipilova, I. V Ionov, E.A. Smolyanskiy, A.L. Lauk, G.E. Remnev, A.S. Maslov, Scale-up of solid oxide fuel cells with magnetron sputtered electrolyte, *Fuel Cells.* 12 (2017) 378–382. doi:10.1002/fuce.201600227.
- [45] Y. Li, S. Wang, P. Su, Proton-conducting micro-solid oxide fuel cells with improved cathode reactions by a nanoscale thin film gadolinium-doped ceria interlayer, *Sci. Educ.* 6 (2016) 1–9. doi:10.1038/srep22369.
- [46] M. Sriubas, G. Laukaitis, The influence of the technological parameters on the ionic conductivity of samarium doped ceria thin films, *Mater. Sci.* 21 (2015). doi:10.5755/j01.ms.21.1.5700.
- [47] A.P. Kulkarni, S. Giddey, S.P.S. Badwal, Enhancing oxygen reduction reactions in solid oxide fuel cells with ultrathin nanofilm electrode–electrolyte interfacial layers, *J. Phys. Chem. C.* 120 (2016) 15675–15683. doi:10.1021/acs.jpcc.5b09345.

- [48] R.T. Baker, R. Salar, A.R. Potter, I.S. Metcalfe, M. Sahibzada, Influence of morphology on the behaviour of electrodes in a proton-conducting Solid Oxide Fuel Cell, *J. Power Sources*. 191 (2009) 448–455. doi:10.1016/j.jpowsour.2009.02.039.
- [49] T. Sato, T. Inoue, D. Ichinose, H. Funakubo, K. Uchiyama, Fabrication of highly (110)-oriented BaCeO₃-based proton-conductive oxide thin films by RF magnetron sputtering method, *Jpn. J. Appl. Phys.* 55 (2016) 02BC19. doi:10.7567/JJAP.55.02BC19.
- [50] M. Al-hadidi, J.P. Goss, P.R. Briddon, R. Al-hamadany, M.J. Rayson, J.P. Goss, P.R. Briddon, R. Al-hamadany, Association of oxygen vacancies with carbon impurity in strontium titanate: first principles calculations, *Ferroelectrics*. 497 (2016) 9–14. doi:10.1080/00150193.2016.1160469.
- [51] P. Yan, A. Mineshige, T. Mori, Y. Wu, G.J. Auchterlonie, J. Zou, J. Drennan, Microanalysis of a grain boundary 's blocking effect in lanthanum silicate electrolyte for intermediate-temperature solid oxide fuel cells, *Appl. Mater. Interfaces*. 5 (2013) 5307–5313.
- [52] C. Li, C. Li, X. Ning, Performance of YSZ electrolyte layer deposited by atmospheric plasma spraying for cermet-supported tubular SOFC, *73* (2004) 699–703. doi:10.1016/j.vacuum.2003.12.096.
- [53] P. Tiwari, S. Basu, Performance studies of electrolyte-supported solid oxide fuel cell with Ni-YSZ and Ni-TiO₂-YSZ as anodes, (2014) 805–812. doi:10.1007/s10008-013-2326-6.
- [54] J. Jiang, X. Hu, N. Ye, J.L. Hertz, Microstructure and ionic conductivity of yttria-stabilized zirconia thin films deposited on MgO, *J. Am. Ceram. Soc.* 97 (2014) 1131–1136. doi:10.1111/jace.12740.
- [55] A. Evans, A. Bieberle-Hütter, H. Galinski, J.L.M. Rupp, T. Ryll, B. Scherrer, R. Tölke, L.J. Gauckler, Micro-solid oxide fuel cells: Status, challenges, and chances, *Monatshefte Fur Chemie*. 140 (2009) 975–983. doi:10.1007/s00706-009-0107-9.
- [56] L.S. Wang, S.A. Barnett, Sputter-deposited medium-temperature solid oxide fuel cells with multi-layer electrolytes, *Solid State Ionics*. 61 (1993) 2–5.
- [57] L.S. Wang, E.S. Thiele, S.A. Barnett, Sputter deposition of yttria-stabilized zirconia and silver cermet electrodes for SOFC applications, *Solid State Commun.* 52 (1992) 261–267.

- [58] T. Götsch, W. Wallisch, M. Stöger-pollach, B. Klötzer, S. Penner, T. Götsch, W. Wallisch, M. Stöger-pollach, B. Klötzer, S. Penner, From zirconia to yttria : Sampling the YSZ phase diagram using sputter-deposited thin films From zirconia to yttria : Sampling the YSZ phase diagram using sputter-deposited thin films, *AIP Adv.* 6 (2016). doi:10.1063/1.4942818.
- [59] M. Biswas, K.C. Sadanala, Electrolyte materials for solid oxide fuel cell powder metallurgy & mining electrolyte materials for solid oxide fuel cell, *J. Powder Metall. Min.* 2 (2018). doi:10.4172/2168-9806.1000117.
- [60] B.S. Prakash, S.S. Kumar, S.T. Aruna, Properties and development of Ni / YSZ as an anode material in solid oxide fuel cell : A review, *Renew. Sustain. Energy Rev.* 36 (2014) 149–179. doi:10.1016/j.rser.2014.04.043.
- [61] R. Antunes, J. Jewulski, T. Golec, Full Parametric Characterization of LSM / LSM-YSZ Cathodes by Electrochemical Impedance Spectroscopy, *J. Fuel Cell Sci. Technol.* 11 (2019) 1–7. doi:10.1115/1.4025533.
- [62] E. Navickas, M. Gerstl, G. Friedbacher, F. Kubel, J. Fleig, Measurement of the across-plane conductivity of YSZ thin films on silicon, *Solid State Ionics.* 211 (2012) 58–64. doi:10.1016/j.ssi.2012.01.007.
- [63] K.V.L. V Narayanachari, S. Raghavan, Stress and texture development during sputtering of yttria, zirconia, and yttria stabilized zirconia films on Si substrates, *J. Appl. Phys.* 112 (2012). doi:10.1063/1.4757924.
- [64] M. Sillassen, P. Eklund, M. Sridharan, N. Pryds, N. Bonanos, J. Bøttiger, Ionic conductivity and thermal stability of magnetron-sputtered nanocrystalline yttria-stabilized zirconia, *J. Appl. Phys.* 105 (2009). doi:10.1063/1.3130404.
- [65] S. Hong, H. Yang, Y. Lim, Y.B. Kim, Microstructure-controlled deposition of yttria-stabilized zirconia electrolyte for low temperature solid oxide fuel cell performance stability enhancement, *Thin Solid Films.* 618 (2016) 207–212. doi:10.1016/j.tsf.2016.06.001.
- [66] F. Smeacetto, M. Salvo, L.C. Ajitdoss, S. Perero, T. Moskalewicz, S. Boldrini, L. Doubova, M. Ferraris, Yttria-stabilized zirconia thin film electrolyte produced by RF sputtering for solid oxide fuel cell applications, *Mater. Lett.* 64 (2010) 2450–2453. doi:10.1016/j.matlet.2010.08.016.

- [67] J.H. Shim, J.S. Park, J. An, T.M. Gür, S. Kang, F.B. Prinz, Intermediate-temperature ceramic fuel cells with thin film yttrium-doped barium zirconate electrolytes, *Chem. Mater.* 21 (2009) 3290–3296. doi:10.1021/cm900820p.
- [68] X. Tan, S. Xu, L. Zhang, F. Liu, B.A. Goodman, W. Deng, Preparation and optical properties of Ho³⁺ doped YSZ single crystals, *Appl. Phys. A.* 124 (2018) 1–7. doi:10.1007/s00339-018-2284-z.
- [69] B.P. Dhonge, T. Mathews, S. Rajagopa, S. Dash, S. Dhara, A.K. Tyagi, Cubic fluorite yttria stabilized zirconia (YSZ) film synthesis by combustion chemical vapour deposition (C-CVD), *Proc. Int. Conf. Nanosci. Eng. Technol. ICONSET 2011.* (2011) 65–68.
- [70] J. Yang, H. Zhao, X. Zhong, F. Shao, C. Liu, Thermal cycling behavior of quasi-columnar YSZ coatings deposited by PS-PVD, *J. Therm. Spray Technol.* 26 (2017) 132–139. doi:10.1007/s11666-016-0491-8.
- [71] A.V.D. Satish Tailor, Manoj Singh, R.M. Mohanty, Microstructural and thermal properties of plasma sprayed YSZ nano-clusters thermal barrier coatings, *J. Clust. Sci.* 27 (2016) 1501–1518. doi:10.1007/s10876-016-1025-8.
- [72] H.U. Anderson, I. Kosacki, Microstructure-property relationships in nanocrystalline oxide thin films, *Ionics (Kiel).* 6 (2000) 294–311. doi:10.1007/BF02374080.
- [73] S. Somacescu, M. Florea, P. Osiceanu, J. Maria, C.C. Ghica, J. Manuel, Ni-doped (CeO_{2-d})–YSZ mesoarchitected with nanocrystalline framework : the effect of thermal treatment on structure , surface chemistry and catalytic properties in the partial oxidation of methane (CPOM), *J. Nanoparticle Res.* 17 (2015) 1–16. doi:10.1007/s11051-015-3206-z.
- [74] A.P. Naumenko, N.I. Berezovska, M.M. Biliy, O. V Shevchenko, Vibrational analysis and raman spectra of tetragonal zirconia, *Phys. Chem. Solid State.* 9 (2008) 121–125.
- [75] B. Bagchi, R.N. Basu, A simple sol-gel approach to synthesize nanocrystalline 8 mol% yttria stabilized zirconia from metal-chelate precursors: Microstructural evolution and conductivity studies, *J. Alloys Compd.* 647 (2015) 620–626. doi:10.1016/j.jallcom.2015.06.082.

- [76] D. Das, B. Bagchi, R.N. Basu, Nanostructured zirconia thin film fabricated by electrophoretic deposition technique, *J. Alloys Compd.* 693 (2017) 1220–1230. doi:10.1016/j.jallcom.2016.10.088.
- [77] J. Molina-Reyes, H. Tiznado, G. Soto, M. Vargas-Bautista, D. Dominguez, E. Murillo, D. Sweeney, J. Read, Physical and electrical characterization of yttrium-stabilized zirconia (YSZ) thin films deposited by sputtering and atomic-layer deposition, *J. Mater. Sci. Mater. Electron.* 0 (2018) 1–9. doi:10.1007/s10854-018-8909-3.
- [78] N. Duan, H. Lin, L. Li, J. Hu, L. Bi, H. Lu, J. Xie, L. Deng, ZrO₂-TiO₂ thin films: a new material system for mid-infrared integrated photonics, *Opt. Mater. Express.* 3 (2013) 154–159. doi:10.1364/OME.3.015370.
- [79] D.A. Macedo, *Infrared Spectroscopy Techniques in the Characterization of SOFC Functional Ceramics*, InTech, 2010.
- [80] S.S. Chopade, C. Nayak, D. Bhattacharyya, S.N. Jha, R.B. Tokas, N.K. Sahoo, M.N. Deo, a. Biswas, S. Rai, K.H. Thulasi Raman, G.M. Rao, N. Kumar, D.S. Patil, RF plasma enhanced MOCVD of yttria stabilized zirconia thin films using octanedionate precursors and their characterization, *Appl. Surf. Sci.* 355 (2015) 82–92. doi:10.1016/j.apsusc.2015.07.090.
- [81] K.S. Sree Harsha, *Principles of Vapor Deposition of Thin Films*, 2006. doi:10.1016/B978-008044699-8/50012-7.
- [82] Y.Y. Choi, D.J. Choi, Investigating and understanding the initial growth, *Cryst Eng Comm.* 15 (2013) 6963–6970. doi:10.1039/c3ce40745d.
- [83] B. Henkel, T. Neubert, S. Zabel, C. Lamprecht, C. Selhuber-Unkel, K. Rätzke, T. Strunskus, M. Vergöhl, F. Faupel, Photocatalytic properties of titania thin films prepared by sputtering versus evaporation and aging of induced oxygen vacancy defects, *Appl. Catal. B Environ.* 180 (2016) 362–371. doi:10.1016/j.apcatb.2015.06.041.
- [84] E. Fabbri, D. Pergolesi, E. Traversa, Electrode materials: A challenge for the exploitation of protonic solid oxide fuel cells, *Sci. Technol. Adv. Mater.* 11 (2010). doi:10.1088/1468-6996/11/4/044301.
- [85] S. Sønderby, A. Aijaz, U. Helmersson, K. Sarakinos, P. Eklund, *Surface & Coatings Technology* Deposition of yttria-stabilized zirconia thin films by high power impulse magnetron sputtering and pulsed magnetron sputtering, 240 (2014) 1–6.

- [86] A. Lechuga, H. Momaca, S. Rodríguez, M. Aquino, O. Méndez, High-temperature dependence of low magnetization Mn_5Ge_3 phase formation of sputtered thin films, *Superf. y Vacío*. 30 (2017) 61–64.
- [87] M. Zou, F. Yang, K. Wen, W. Lv, M. Waqas, W. He, Ionic conductivity evolution at strained crystal interfaces in solid oxide fuel cells (SOFCs), *Int. J. Hydrogen Energy*. 41 (2016) 2225–22259.
- [88] J.R. Piascik, J.Y. Thompson, C. a. Bower, B.R. Stoner, Evaluation of crystallinity and film stress in yttria-stabilized zirconia thin films, *J. Vac. Sci. Technol. A Vacuum, Surfaces, Film*. 23 (2005) 1419. doi:10.1116/1.2011403.
- [89] P. Coddet, A. Caillard, J. Vulliet, C. Richard, A.L. Thomann, Multistep magnetron sputtering process and in-situ heat treatment to manufacture thick, fully oxidized and well crystallized YSZ films, *Surf. Coatings Technol.* 349 (2018) 133–143. doi:10.1016/j.surfcoat.2018.05.065.
- [90] J.T. Shilo, J. Pelleg, M. Sinder, J.T. Shilo, J. Pelleg, M. Sinder, Reduced activation energy of nano size phase formation in yttria stabilized zirconia film obtained by RF magnetron sputtering : Preliminary results, *AIP Adv.* 115203 (2018). doi:10.1063/1.5051739.
- [91] Y. Tolstova, S.T. Omelchenko, A.M. Shing, H.A. Atwater, Heteroepitaxial growth of Pt and Au thin films on MgO single crystals by bias-assisted sputtering, *Nat. Publ. Gr.* (2016) 4–9. doi:10.1038/srep23232.
- [92] F. Band, O. Christensen, RF biasing through capacitive collector to target coupling in RF diode sputtering, *J. Phys. E Sci. Instruments RF*. 5 (1972) 86–90.
- [93] S.H. Seo, J.H. In, H.Y. Chang, Effects of a sheath boundary on electron energy distribution in Ar/He dc magnetron discharges, *J. Appl. Phys.* 96 (2004) 57–64. doi:10.1063/1.1755850.
- [94] L. Yao, G. Ou, H. Nishijima, W. Pan, Enhanced conductivity of (110)-textured ScSZ films tuned by an amorphous alumina interlayer, *Phys. Chem. Chem. Phys.* 17 (2015) 23034–23040. doi:10.1039/C5CP03631C.
- [95] M. Tanhaei, M. Mozammel, Yttria-stabilized zirconia thin film electrolyte deposited by EB-PVD on porous anode support for SOFC applications, *Ceram. Int.* 43 (2017) 3035–3042. doi:10.1016/j.ceramint.2016.11.097.

- [96] T. Yeh, R. Lin, B. Cherng, J. Cherng, Effects of sputtering mode on the microstructure and ionic conductivity of yttria-stabilized zirconia films, *J. Cryst. Growth.* 489 (2018) 57–62. doi:10.1016/j.jcrysgro.2018.02.039.
- [97] Y.H. Lee, G.Y. Cho, I. Chang, S. Ji, Y.B. Kim, S.W. Cha, Platinum-based nanocomposite electrodes for low-temperature solid oxide fuel cells with extended lifetime, *J. Power Sources.* 307 (2016) 289–296. doi:10.1016/j.jpowsour.2015.12.089.
- [98] J. Park, Y. Lee, I. Chang, G.Y. Cho, S. Ji, W. Lee, S.W. Cha, Atomic layer deposition of yttria-stabilized zirconia thin films for enhanced reactivity and stability of solid oxide fuel cells, *Energy.* 116 (2016) 170–176. doi:10.1016/j.energy.2016.09.094.
- [99] J.S. Lamas, W.P. Leroy, Y.G. Lu, J. Verbeeck, G. Van Tendeloo, D. Depla, Using the macroscopic scale to predict the nano-scale behavior of YSZ thin films, *Surf. Coatings Technol.* 238 (2014) 45–50. doi:10.1016/j.surfcoat.2013.10.034.
- [100] P. Briois, E. Gourba, A. Billard, A. Ringuedé, M. Cassir, Microstructure - Electrical properties relationship of YSZ thin films reactively sputter-deposited at different pressures, *Ionics (Kiel).* 11 (2005) 301–305. doi:10.1007/BF02430393.
- [101] Y.S. Wang, Haiqian., Weijie, Ji., Lei Zhang., Yunhui Gong., Bin Xie., Preparation of YSZ films by magnetron sputtering for anode-supported SOFC, *Solid State Ionics.* 192 (2011) 413–418. doi:10.1016/j.ssi.2010.05.022.
- [102] S. Ji, W.H. Tanveer, W. Yu, S. Kang, G.Y. Cho, S.H. Kim, J. An, S.W. Cha, Surface engineering of nanoporous substrate for solid oxide fuel cells with atomic layer-deposited electrolyte, *Beilstein J. Nanotechnol.* 6 (2015) 1805–1810. doi:10.3762/bjnano.6.184.
- [103] S. Ji, J. Ha, T. Park, Y. Kim, B. Koo, Y.B. Kim, Substrate-dependent growth of nanothin film solid oxide fuel cells toward cost-effective nanostructuring, *Int. J. Precis. Eng. Manuf. Technol.* 3 (2016) 35–39. doi:10.1007/s40684-016-0005-7.
- [104] S. Ji, I. Chang, Y.H. Lee, J. Park, J.Y. Paek, M.H. Lee, S.W. Cha, Fabrication of low-temperature solid oxide fuel cells with a nanothin protective layer by

- atomic layer deposition, *Nanoscale Res. Lett.* 8 (2013) 1–7. doi:10.1186/1556-276X-8-48.
- [105] H.M. Moghaddam, S. Nasirian, Dependence of activation energy and lattice strain on TiO₂ nanoparticles, *J. Exp. Nanoscience.* 1 (2012) 201–212. doi:10.1080/17458080.2011.620023.
- [106] X. Ren, W. Pan, Mechanical properties of high-temperature-degraded yttria-stabilized zirconia, *Acta Mater.* 69 (2018) 397–406. doi:10.1016/j.actamat.2014.01.017.
- [107] Y. Zhao, J. Zhang, Microstrain and grain-size analysis from diffraction peak width and graphical derivation of high- pressure thermomechanics research papers, *Appl. Crystallography.* 41 (2008) 1095–1108. doi:10.1107/S0021889808031762.
- [108] S. Mahieu, P. Ghekiere, D. Depla, R. De Gryse, O.I. Lebedev, G. Van Tendeloo, Mechanism of in-plane alignment in magnetron sputtered biaxially aligned yttria-stabilized zirconia, *J. Cryst. Growth.* 290 (2006) 272–279. doi:10.1016/j.jcrysgro.2005.12.093.
- [109] J. Li, N. Zhang, Z. He, K. Sun, Z. Wu, Preparation and characterization of one-dimensional nano-structured composite cathodes for solid oxide fuel cells, *J. Alloys Compd.* 663 (2015) 664–671. doi:10.1016/j.jallcom.2015.12.166.
- [110] I.H. Jung, K.K. Bae, K.C. Song, M.S. Yang, S.K. Ihm, Columnar grain growth of yttria-stabilized-zirconia in inductively coupled plasma spraying, *J. Therm. Spray Technol.* 13 (2004) 544–553. doi:10.1361/10599630419382.
- [111] Z.M. Rosli, K.W. Loon, J.M. Juoi, N. Nayan, Z.B. Mahamud, Y. Yusuf, Characterization of TiAlBN nanocomposite coating deposited via radio frequency magnetron sputtering using single hot-pressed target, *Adv. Mater. Res.* 626 (2012) 298–301. doi:10.4028/www.scientific.net/AMR.626.298.
- [112] X. Zhao, J. Jin, J.C. Cheng, J.W. Lee, K.H. Wu, K.C. Lin, J.R. Tsai, K.C. Liu, Structural and optical properties of zirconia thin films deposited by reactive high-power impulse magnetron sputtering, *Thin Solid Films.* 570 (2014) 404–411. doi:10.1016/j.tsf.2014.05.060.
- [113] D. Stender, R. Frison, K. Conder, J.L.M. Rupp, B. Scherrer, J.M. Martynczuk, L.J. Gauckler, C.W. Schneider, T. Lippert, A. Wokaun,

- Crystallization of zirconia based thin films, *Phys. Chem. Chem. Phys.* 17 (2015) 18613–18620. doi:10.1039/C5CP02631H.
- [114] G.H. Jaffari, A. Imran, M. Bah, A. Ali, A.S. Bhatti, U. Saeed, S.I. Shah, Identification and quantification of oxygen vacancies in CeO₂ nanocrystals and their role in formation of F-centers, *Appl. Surf. Sci.* 396 (2017) 547–553. doi:10.1016/j.apsusc.2016.10.193.
- [115] L. Kurpaska, M. Frelek-Kozak, K. Nowakowska-Langier, M. Lesniak, J. Jasinski, J. Jagielski, Structural and mechanical properties of Ar-ion irradiated YSZ single-crystals grown in different crystallographic orientations, *Nucl. Instruments Methods Phys. Res. Sect. B Beam Interact. with Mater. Atoms.* 409 (2017) 81–85. doi:10.1016/j.nimb.2017.05.008.
- [116] R.W. Liu Qu, Kwang-Leong Choy, Theoretical and experimental studies of doping effects on thermodynamic properties of (D_y,Y)-ZrO₂, *Acta Mater.* 114 (2016) 7–14. doi:https://doi.org/10.1016/j.actamat.2016.04.007.
- [117] A. Maghsoudipour, L.M. Gorjani, F. Hashemzadeh, Synthesis and characterization of cubic yttria-stabilized zirconia (8YSZ) nanoparticles by a modified sol-gel route using sucrose and pectin as organic precursors, *Int. J. Phys. Sci.* 6 (2011) 2518–2525. doi:10.5897/IJPS10.690.
- [118] H.P. Dasari, J.S. Ahn, K. Ahn, S. Park, J. Hong, H. Kim, K.J. Yoon, J. Son, H. Lee, J. Lee, Synthesis , sintering and conductivity behavior of ceria-doped Scandia-stabilized zirconia, *Solid State Ionics.* 263 (2014) 103–109. doi:10.1016/j.ssi.2014.05.013.
- [119] S. Heiroth, T. Lippert, A. Wokaun, M. Döbeli, J.L.M. Rupp, B. Scherrer, L.J. Gauckler, Yttria-stabilized zirconia thin films by pulsed laser deposition: Microstructural and compositional control, *J. Eur. Ceram. Soc.* 30 (2010) 489–495. doi:10.1016/j.jeurceramsoc.2009.06.012.
- [120] C. Ko, K. Kerman, S. Ramanathan, Ultra-thin film solid oxide fuel cells utilizing un-doped nanostructured zirconia electrolytes, *J. Power Sources.* 213 (2012) 343–349. doi:10.1016/j.jpowsour.2012.04.034.
- [121] S. Akasaka, Thin film YSZ-based limiting current-type oxygen and humidity sensor on thermally oxidized silicon substrates, *Sensors Actuators, B Chem.* 236 (2016) 499–505. doi:10.1016/j.snb.2016.06.025.

- [122] T. Maridurai, D. Balaji, S. Sagadevan, Synthesis and characterization of yttrium stabilized zirconia nanoparticles, *Mater. Res.* 19 (2016) 812–816. doi:<http://dx.doi.org/10.1590/1980-5373-MR-2016-0196>.
- [123] M. Hajizadeh-Oghaz, R. Shoja Razavi, M.R. Loghman-Estarki, Synthesis and characterization of non-transformable tetragonal YSZ nanopowder by means of Pechini method for thermal barrier coatings (TBCs) applications, *J. Sol-Gel Sci. Technol.* 70 (2014) 6–13. doi:10.1007/s10971-014-3266-z.
- [124] E. Djurado, F. Boulc'h, L. Dessemond, N. Rosman, M. Mermoux, Study on aging of tetragonal zirconia by coupling impedance and raman spectroscopies in water vapor atmosphere, *J. Electrochem. Soc.* 151 (2004) 774–780. doi:10.1149/1.1697401.
- [125] I. Kaus, P.I. Dahl, J. Mastin, T. Grande, M. Einarsrud, Synthesis and characterization of nanocrystalline YSZ powder by smoldering combustion synthesis, *J. Nano.* (2006) 1–7. doi:10.1155/JNM/2006/49283.
- [126] A.A. Solovyev, A. V. Shipilova, I. V. Ionov, A.N. Kovalchuk, S. V. Rabotkin, V.O. Oskirko, Magnetron-sputtered YSZ and CGO electrolytes for SOFC, *J. Electron. Mater.* 45 (2016) 3921–3928. doi:10.1007/s11664-016-4462-0.
- [127] T. Suzuki, T. Suzuki, T. Yamaguchi, H. Sumi, Fabrication and characterization of YSZ thin films for SOFC application, *J. Ceram. Soc. Japan.* 123 (2015) 250–253. doi:10.2109/jcersj2.123.250.
- [128] G. Laukaitis, J. Dudonis, D. Milcius, Deposition of YSZ thin films using electron beam evaporation technique, *Mater. Sci.* 11 (2005) 268–271.
- [129] D. Pumiglia, D. Pumiglia, S. Vaccaro, A. Masi, S.J. Mcphail, Aggravated test of intermediate temperature solid oxide fuel cells fed with tar-contaminated syngas, *J. Power Sources.* 340 (2017) 150–159. doi:10.1016/j.jpowsour.2016.11.065.
- [130] S. Salari, F.E. Ghodsi, A significant enhancement in the photoluminescence emission of the Mg doped ZrO₂ thin films by tailoring the effect of oxygen vacancy, *J. Lumin.* 182 (2017) 289–299. doi:10.1016/j.jlumin.2016.10.035.
- [131] T. Xiufeng, Effects of the annealing heating rate on sputtered aluminum oxide films, *J. Wuhan Univ. Technol. Sci.* 32 (2017) 94–99. doi:10.1007/s11595-017-1565-2.

- [132] Y.B. Xu, Z.F. Kang, Y. Fan, L.L. Xiao, Q.R. Bo, T.Z. Ding, Electrical properties of the YSZ/STO/YSZ-STO superlattice electrolyte film at low temperatures, *Russ. J. Phys. Chem. A.* 90 (2016) 485–490. doi:10.1134/S0036024416020369.
- [133] S. Sønderby, A. Aijaz, U. Helmersson, K. Sarakinos, P. Eklund, Deposition of yttria-stabilized zirconia thin films by high power impulse magnetron sputtering and pulsed magnetron sputtering, *Surf. Coatings Technol.* 260 (2014) 1–6. doi:10.1016/j.surfcoat.2013.12.001.
- [134] D. Wojcieszak, D. Kaczmarek, M. Mazur, Photocatalytic properties of transparent TiO₂ coatings doped with neodymium, *Polish J. Chem. Technol.* 14 (2012) 1–7.
- [135] X. Quan, B. Sun, H. Xu, Anode decoration with biogenic Pd nanoparticles improved power generation in microbial fuel cells, *Electrochim. Acta.* 182 (2015) 815–820. doi:10.1016/j.electacta.2015.09.157.
- [136] H. Sun, W. Ma, J. Yu, X. Chen, W. Sen, Y. Zhou, Preparation and characterization of La_{0.9}Sr_{0.1}Ga_{0.8}Mg_{0.2}O_{3-δ} thin film electrolyte deposited by RF magnetron sputtering on the porous anode support for IT-SOFC, *Vacuum.* 86 (2012) 1203–1209. doi:10.1016/j.vacuum.2011.11.002.
- [137] Z. Zheng, J. Luo, Q. Li, Mechanism of competitive grain growth in 8YSZ splats deposited by plasma spraying, *J. Therm. Spray Technol.* 24 (2015) 885–891. doi:10.1007/s11666-015-0243-1.
- [138] Y.H. Lee, I. Chang, G.Y. Cho, J. Park, W. Yu, W.H. Tanveer, Thin film solid oxide fuel cells operating below 600 °C: A review, *Int. J. Precis. Eng. Manuf. - Green Technol.* 5 (2018) 441–442. doi:10.1007/s40684-018-0047-0.
- [139] J. Bae, I. Chang, S. Kang, S. Hong, S.W. Cha, Y.B. Kim, Post-annealing of thin-film yttria stabilized zirconia solid oxide fuel cells, *J. Nanosci. Nanotechnology.* 14 (2014) 9294–9299. doi:10.1166/jnn.2014.10121.
- [140] Y. Duan, M. Zhang, L. Wang, F. Wang, L. Yang, X. Li, C. Wang, Plasmonic Ag-TiO_{2-x} nanocomposites for the photocatalytic removal of NO under visible light with high selectivity: The role of oxygen vacancies, *Appl. Catal. B Environ.* 204 (2017) 67–77. doi:10.1016/j.apcatb.2016.11.023.
- [141] Z. Shi, P. Shum, Z. Zhou, L.K.Y. Li, Effect of oxygen flow ratio on the wetting behavior, microstructure and mechanical properties of

- CeO_{2-x}coatings prepared by magnetron sputtering, *Surf. Coatings Technol.* 320 (2017) 333–338. doi:10.1016/j.surfcoat.2016.12.055.
- [142] Y.W. Zhang, Y. Yang, S. Jin, C.S. Liao, C.H. Yan, Doping effect on the grain size and microstrain in the sol-gel-derived rare earth stabilized zirconia nanocrystalline thin films, *J. Mater. Sci. Lett.* 21 (2002) 943–946. doi:10.1023/A:1016025723519.
- [143] V. Vonk, N. Khorshidi, A. Stierle, Structure and oxidation behavior of nickel nanoparticles supported by YSZ(111), *J. Phys. Chem. C.* 121 (2017) 2798–2806. doi:10.1021/acs.jpcc.6b11342.

LIST OF PUBLICATIONS

Journal with Impact Factor

1. **N.A. Rusli.**, R. Muhammad., S. K. Ghoshal., H. Nur., & N. Nayan. (2020). Annealing temperature induced improved crystallinity of YSZ thin film. *Materials Research Express*, 7(5). <https://doi.org/10.1088/2053-1591/ab9039> (**Q2, IF: 1.41**).
2. **Ahmad Rusli, Nurhamizah.**, Muhammad, Rosnita., Ghoshal, Sib., Nur, Hadi., Nafarizal, Nayan., & Jaafar, Siti. (2019). Bias voltage dependent structure and morphology evolution of magnetron sputtered YSZ thin film: A basic insight. *Materials Research Express*, 6(10). <https://doi.org/10.1088/2053-1591/ab3907> 2018 (**Q2, IF: 1.449**).
3. **Nurhamizah, A.R.**, Ibrahim, Zuhairi., Rosnita, Muhammad., Yussof, Wahab & Sakrani, Samsudi. (2017). Effect of annealing temperature on platinum/YSZ thin film fabricated using RF and DC Magnetron Sputtering, *Solid State Phenomena*, 268, 229-233. [10.4028/www.scientific.net/SSP.268.229](https://doi.org/10.4028/www.scientific.net/SSP.268.229) (**Q3, IF: 0.17**).

Indexed Conference Proceedings

1. **N.A. Rusli.**, Z. Ibrahim., R. Muhammad., Y. Wahab., & S. Sakrani. (2018) Review: Development of platinum electrode for low temperature solid oxide fuel cells. *eProceedings Chemistry*, 3, 5-8, eISSN 2550-145.

Non-Indexed Conference Proceedings

1. **N. A. Rusli.**, R. Muhammad., S. K. Ghoshal., & H. Nur. (2017). Effect of oxygen ratio on YSZ thin film deposited using RF magnetron sputtering. NanoMITe Annual Symposium (NMAS 2017) on 14 - 15 November 2017 in UPM Serdang, Malaysia.

2. **N. A. Rusli.**, R. Muhammad., S. K. Ghoshal., H. Nur., & N. Nayan. (2019). Annealing Temperature Induced Improved Crystallinity of YSZ Thin Film. 7th International Conference and Workshop on Basic and Applied Sciences (ICOWOBAS 2019) on 19 July 2019 in KSL Resort Johor Bahru, Malaysia.